

**OS3: The Second International Symposium on Integrated Flow Science IV
Advanced Semiconductor and Digital Transformation**

November 19, 2024

EX-2

- OS3-1 **High-efficiency GaN Micro-LEDs Fabricated by Neutral Beam Etching for VR/AR Applications** *(Invited)*
13:10-13:40 Xuelun Wang (National Institute of Advanced Industrial Science and Technology, Japan), Daisuke Ohori (Tohoku University, Japan), Seiji Samukawa (National Yang Ming Chiao Tung University, Taiwan)
- OS3-2 **Atomic Layer Technology and Its Application for Advanced Heterogeneous Integrated Nano-device = Emerging Plasma Nanotechnology=.** *(Invited)*
13:40-14:10 Seiji Samukawa (National Yang Ming Chiao Tung University, Taiwan)
- OS3-3 **Estimation of Carrier Mobility in Si-Nanopillar/SiGe Composite Films by Laser Heterodyne Photothermal Displacement Measurements under Electric Field**
14:10-14:25 Yoshito Uno, Tomoki Harada (University of Miyazaki, Japan), Daisuke Ohori, Kazuhiko Endo (Tohoku University, Japan), Seiji Samuakwa (National Yang Ming Chiao Tung University, Taiwan / Tohoku University, Japan), Tetsuo Ikari, Atsuhiko Fukuyama (University of Miyazaki, Japan)
- OS3-4 **Epitaxial Growth of High-quality Mg_3Sb_2 -based Thin Films and Their Thermoelectric Properties**
14:25-14:40 Akito Ayukawa, Nozomu Kiridoshi, Takeru Kuriyama (Ibaraki University, Japan), Wakaba Yamamoto, Akira Yasuhara (JEOL Ltd., Japan), Haruhiko Uono, Shunya Sakane (Ibaraki University, Japan)
- OS3-5 **Volume of Fluid Modeling of a Rotating Disk Edge Wetting with Backside Dispense** *(Invited)*
14:50-15:20 Alberto Ceschin (SCREEN SPE Germany GmbH, Germany), Mizuki Kihara, Masanobu Sato (SCREEN Semiconductor Solutions Co., Ltd, Japan), Naser Belmiloud, Karim Huet (SCREEN SPE Germany GmbH, Germany)
- OS3-6 **Evaluation of the Germination Process of the *Haworthia cooperi* ver. *Truncate* Under the Controllable Gas Plasma Radiation**
15:20-15:35 Akihiro Kanbara (The graduate school for the creation of new photonics industries, Japan), Daisuke Ohori (Tohoku University, Japan), Neisei Hayashi (The graduate school for the creation of new photonics industries, Japan)
- OS3-7 **Interface Design Concept of HfO_2/Si Gate Stack for Nanosheet MOSFETs**
15:35-15:50 Yukinori Morita, Hiroyuki Ota, Shinji Migita (National Institute of Advanced Industrial Science and Technology (AIST), Japan)
- OS3-8 **Effect of Oxygen Vacancies at the AZO/ZnO Interface on ReRAM Characteristics**
15:50-16:05 Kosei Hamada, Takeo Ohno, Kana Minami (Oita University, Japan), Kazuhiko Endo (Tohoku University, Japan)